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ZnTe and (Cd,Mg)Te layers as a contact for the high-resistivity (Cd,Mn)Te

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Introdution

The II-VI semiconductors with resistivity above 10⁹ Ω cm suffer from the ohmic contacting problem due to their electron affinity and relatively large work function high compering to metals. To solve the problem of work function mismatch an amorphous layer between a semiconductor and metal junction was proposed by Sebestyen [1]. Such layers with a high density of defects provide better charge transport between metal and semiconductor material. We will present our recent results obtained from (Cd,Mn)Te samples with resistivity in the range 10⁹-10¹⁰ Ω cm. this work, we want to focus on In amorphous/polycrystalline layers. ZnTe, ZnTe:Sb, ZnTe:In and (Cd,Mg)Te, (Cd,Mg)Te:Sb, (Cd,Mg)Te:In layers were deposited in MBE chamber and covered by AuPd layer.





Layer deposition: ZnTe cell at T=660°C Growth rate approx. 8.6 nm/min

10⁴

10³

Intensity [cps]

10⁰

10⁻¹

10⁻²

We observe columnar growth

Voltage (V)

Voltage (V)

Voltage (V)

CMT:In = $Cd_{0.95}Mn_{0.05}Te:In [In ~10^{17}cm^{-3}], CMT:In,V = Cd_{0.95}Mn_{0.05}Te:In,V [In ~10^{17}cm^{-3}], V ~10^{12}cm^{-3}]$

(Cd,Mg)Te layer (SEM and XRD observations)

(Cd,Mg)Te layers deposited on (Cd,Mn)Te (Cd,Mg)Te:Sb layer (Cd,Mg)Te layer (Cd,Mg)Te:In layer (Cd,Mg)Te layer (Cd,Mg)Te cell at T=684 °C Depotition time: 15 min. ■ 5380_1A with rings ■ 5355_5B with rings 5380_2A_CdMgTe:In 4×10⁻⁸ CMT:In,V/CdMgTe:Sb/AuPd 4×10⁻⁸ CMT:In/CdMgTe/AuPd 4×10⁻⁸ · with rings CMT:In,V/CdMgTe:In/AuPd (A/cm2) (A/cm2) 5376_2B (Cd,Mn)Te nsity (A/cm2) with small grain in 2×10⁻⁸ 2×10⁻⁸ 2×10⁻⁸ corner PAN-ON4 7.0kV 7.1mm x120k SE(U) Density Density - CdMnTe without layer CdMnTe with CdMgTe layer 111 Current Current O Current I Current I Ortrent Ortrent O 333 222 -4×10⁻⁸ -4×10⁻⁸ -4×10⁻⁸ -10 Voltage (V Voltage (V 400 600 800 1000 -1000-800 -600 -400 -200 200 -1000-800 -600 -400 -200 0 200 400 600 800 1000 0 -1000-800 -600 -400 -200 200 400 600 800 1000 0 Voltage (V) Voltage (V) Voltage (V)



Summary:

- Metal/(Cd,Mn)Te contact shows Schottky I-V characteristic.
- Non-linear (",Schottky") behavior of I-V characteristic on (Cd,Mn)Te with ZnTe:Sb/AuPd contact layer.
- The SEM and TEM measurements prove the "columnar" growth of ZnTe layers. We observe some degree of amorphization of ZnTe layers.
- We obtained "columnar" (Cd,Mg)Te layers .
- Quasi-linerar I-V characteristics for CdMgTe/AuPd layers were obtained



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Narodowe Centrum Badań i Rozwoju

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